

IN THE CLAIMS:

Please amend the claims as follows:

1. (currently amended) A method of manufacturing a metallic film consisting essentially of a giant single crystal grain, consisting essentially of the steps of:
 - depositing the metallic film directly on a substrate in an atmosphere of an inert gas and a specified additive gas to change a surface energy, grain boundary energy, or internal strain energy of the metallic film; and
 - annealing the resultant metallic film of the first step at a temperature suitable for carrying out a grain growth of the metallic film containing the additive gas and controlling the grain size of the giant crystal grain so the giant single crystal grain has a grain size with a ratio of thickness to an average grain size of the metallic film of more than 50 to 1.
2. (original) In the method as claimed in claim 1, the change of the surface energy, grain boundary energy, or internal strain energy of the metallic film is performed by incorporating the additive gas to the metallic film, or production of a compound between the additive gas and the metallic film.
3. (previously presented) The method as claimed in claim 1, wherein the deposition of the metallic film is performed by a process selected from the group consisting of a DC/RF magnetron sputtering, DC/RF sputtering, metal organic chemical vapor deposition, vacuum evaporation, laser ablation, ionized beam deposition, and electroplating.

4. (previously presented) The method as claimed in claim 1, wherein the additive gas is selected from the group consisting of O₂, N₂+O₂, N₂O, Cl, and N₂.

5. (previously presented) The method as claimed in claim 1, wherein the metallic film is selected from the group consisting of Pt, Au, Cu, Al, Ni, Ag, Ir, Pd, Ti, Ru, Ta, W, Os, and Rh.

6-8. (canceled)

9. (currently amended) A method of manufacturing a metallic film comprising a single crystal grain comprising the steps of:

depositing a metallic film on a substrate while controlling the grain size of the single crystal grain and annealing the metallic film so that the single crystal grain has a grain size with a ratio of thickness to an average grain size of the metallic film of over more than 50 to 1;
and annealing the film.